

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) BU9-98-225		Application Number Not Yet Assigned 09/883 981		
				Applicant(s) Andrews et al.				
				Filing Date Concurrently Herewith		Group Art Unit 2813 Not Yet Assigned		
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
		5,175,127	12/29/92	Manning				
		5,316,965	05/31/94	Philipossian et al.				
		5,646,063	07/08/97	Mehta et al.				
		5,702,976	12/30/97	Schuegraf et al.				
		5,719,085	02/17/98	Moon et al.				
		5,721,173	02/24/98	Yano et al.				
		5,729,043	03/17/98	Shepard				
		5,741,740	04/21/98	Jang et al.				
FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
		Anonymous, "Sensitive Surface Damage Avoidance During Polishing", Research Disclosure, Kenneth Mason Publications Limited, November 1991, Number 331.						
		Pye et al., "High-density plasma CVD and CMP for 0.25-um intermetal dielectric processing" Solid State Technology, December 1995, pages 65-72.						
EXAMINER 				DATE CONSIDERED 8/28/01				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

INFORMATION DISCLOSURE CITATION

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Docket Number (Optional)

BU9-98-225 21V

Application Number

Not Yet Assigned

Applicant(s)

Andrews et al.

Filing Date

Concurrently Herewith

Group Art Unit

Not Yet Assigned

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
DB		5,298,450	03/29/94	Verret			
		6,048,775	04/11/00	Yao et al.			
		6,048,771	04/11/00	Lin et al.			
		6,159,822	12/12/00	Yang et al.			
		5,872,043A	02/1999	Chen			
		5,728,621	03/1998	Zheng et al.			

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
DB		DE-019741704A1	09/1997	Germany				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

DB		Moreau, Wayne M., "Semiconductor Lithography Principles, Practices, and Materials", Microdevices Physics and Fabrication Technologies, 1987, pages 720-729.

EXAMINER

DB

DATE CONSIDERED

8/28/01

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